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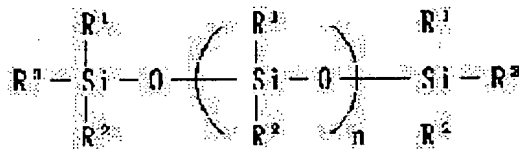
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NAKAMURA GENICHI**(54) SKIN-PROTECTIVE COSMETIC****(57)Abstract:**

**PROBLEM TO BE SOLVED:** To obtain a skin-protective cosmetic containing a specific polysiloxane, excellent in the softness and smoothness when applied to the skin, with no oily feeling remaining on the skin even if washed at high temperature, and therefore sustainably having favorable use feeling.

**SOLUTION:** This skin-protective cosmetic contains 0.1-80wt.% of a modified polysiloxane of the formula [R<sup>1</sup> and R<sup>2</sup> are each a 1-6C alkyl or a (alkyl- substituted) 6-10C aromatic hydrocarbon; R<sup>3</sup> is a 16-600C saturated hydrocarbon; (n) is 0-3,000] as active ingredient. The average number of the carbon atoms of R<sup>3</sup> (saturated hydrocarbon) is pref. 40-300; if <16, the polysiloxane becomes oily, having inadequate film-forming effect and being poor in compatibility. In contrast, if ≥600, the polysiloxane becomes resinous, deteriorating its formulation into a cosmetic base. If the average value of (n) is ≥100, the percutaneous absorbability and softness of the polysiloxane (this cosmetic) is further improved.

When the weight ratio of the sum of the two saturated hydrocarbon group segments to the remaining polysiloxane segment in R<sup>3</sup> is (30:70) to (1:99), the skin-protective effect and its sustainability of the polysiloxane (this cosmetic) is further improved without impairing cutaneous respiration and water vapor transpiration.

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